Thin film Process : Thin film deposition by Spin coating technique

Equipment : Spin Coating Unit

Photograph :

Basic Principle:

The method involves four different stages for coating:

(1) Deposition of the coating fluid onto the wafer or substrate:

(2) Accelerating the substrate to its final, desired, rotation speed:

(3) Spinning substrate at a constant rate and dominance of fluid viscous forces in fluid thinning, and foams a film.

Capabilities: Manual operation

Sample Requirements: Max. 1" x 1"